

PATENT NUMBER

U.S. UTILITY	Patent Application
0.0.0112111	1 atont replication

M.C. O.I.P.E.

PATENT DATE

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APPLICATION NO.	CONT/PRIOR	CLASS	SUBCLASS	ART UNIT	EXAMINER
09/956916		427	· 1	1762	
Luc Ouell Jonathan	et Lachance				

Method of depositing an optical quality silica film by PECVD

ISSUING CLASSIFICATION

ORIGINAL CROSS REFERENCE(S)

CLASS SUBCLASS CLASS SUBCLASS (ONE SUBCLASS PER BLOCK)

INTERNATIONAL CLASSIFICATION

COntinued on Issue Silp Inside File Jacket

TERMINAL DISCLAIMER	DRAWINGS			CLAIMS ALLOWED		
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.	
☐ The term of this patent				NOTICE OF ALI	LOWANCE MAILED	
subsequent to (date) has been disclaimed.	(Assistant	Examiner)	(Date)	•		
The term of this patent shall						
not extend beyond the expiration date off U.S Patent. No			ISSUE FEE			
				Amount Due	Date Paid	
	(Primary	Examiner)	(Date)			
The terminalmonths of	,			ISSUE BATCH NUMBER		
this patent have been disclaimed.	(Legal instruments Examiner)		(Date)			
WARNING: The information disclosed herein may be res Possession outside the U.S. Patent & Traden	tricted. Unauthorized nark Office is restricted	disclosure may be i	prohibited by the L	United States Code Title 3 tors only.	5, Sections 122, 181 and 368	
orm PTO-436A			FILED WITH:		TFICHE CD-RO	